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## U.S. UTILITY Patent Application

APPL NUM	PILING DATE	CLASS	SUBCLASS	GAU	EX	AMINER		
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**APPLICANTS: Fortin Vincent: Tsai Kuei-Chang?								
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NOTICE OF ALLOWANCE MAILED  ISSUE FEE			CLAIMS ALLOWED			
		Assistant Examiner	Total Claims Print Claim for O.G			
			DRAWING			
Amount Due	Date Paid		Shoots Drwg. Figs.Drwg. Print Fig.			
TERMINAL		Primary Examiner PREPARED FOR ISSUE	Application Examiner			
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